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**Term:**

12 and (reduc\$3 near5 particulates or  
contamination)

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USPT	12 and ((438/714 or 438/905).ccls.)	5	<u>L4</u>
USPT	12 and (reduc\$3 near5 particulates or contamination)	26	<u>L3</u>
USPT	(etch chamber or dry etch chamber) same (change\$3 or reduc\$3 near5 power)	65	<u>L2</u>
USPT	(etch chamber or dry etch chamber) near8 (change\$3 or reduc\$3 power)	20	<u>L1</u>